Applicant : Osterheld et a Serial No. : Unassigned Filed : October 29, 2001

3 46. (New) The polishing pad of claim 46, wherein the grooves have a width between about 0.015 and 0.04 inches.

46. (New) The polishing pad of claim 5, wherein the grooves have a width of approximately 0.02 inches.

(New) The polishing pad of claim 4/5, wherein the grooves have a pitch between about 0.09 and 0.24 inches.

(New) The polishing pad of claim 47, wherein the grooves have a pitch of approximately 0.12 inches.

7 49. (New) The polishing pad of claim 48, wherein the grooves are concentrically arranged.

√50. (New) The polishing pad of claim 45, wherein the grooves are uniformly spaced over the polishing surface.

9 51. (New) The polishing pad of claim 45, wherein the polishing pad further comprises a lower layer on a side of the layer opposite the polishing surface.

10 52. (New) The polishing pad of claim 51, wherein a distance between a bottom of the grooves and the lower layer is between about 0.035 and 0.085 inches.

l \(\frac{1}{5}\)3. (New) The polishing pad of claim \(\frac{5}{5}\), wherein the distance between a bottom of the grooves and the lower layer is about 0.04 inches.

17 54. (New) The polishing pad of claim \$1, wherein the thickness of the layer of is about 0.07 inches.